

132 28. (Amended) A photomask comprising:
a transparent substrate;
a hollow section formed on a surface of said transparent substrate; and
a shade pattern including a shade section, said shade section made up of a shade film and formed in said hollow section, wherein a surface of said transparent substrate and said shade pattern are planarized to form a same surface.

REMARKS

This amendment responds to the Office Action dated December 5, 2000 in which the Examiner rejected claims 1, 2, 5, 7, 9-11, 14, 20, 22 and 28 under 35 U.S.C. § 102(b), rejected claims 1, 2, 5, 7, 9-11, 14 and 28 under 35 U.S.C. § 102(e) and rejected claims 3, 4, 6, 8, 12, 13, 15-19, 21, 23, 24 and 27 under 35 U.S.C. § 103.

As indicated above, claim 1 has been amended to correct a grammatical error.

Claim 1 claims a photomask and claim 16 claims a photomask fabrication method including a transparent substrate, a hollow section formed on the surface of the transparent substrate, a shade pattern formed in the hollow section and reflection preventing sections or films.

Through the structure and method of the claimed invention having reflection preventing sections or films, as claimed in claims 1 and 16, the claimed invention provides a photomask and method of making thereof which has a large mechanical strength and has decreased structural defects in the shade pattern. The prior art does not show, teach or